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## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: KIM et al.

Examiner: PERT, Evan T.

Application No.: 10/813,913

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Title: METHODS AND APPARATUS FOR  
INSPECTING CONTACT OPENINGS IN A PLASMA  
PROCESSING SYSTEM

INFORMATION DISCLOSURE STATEMENT

## US PATENT DOCUMENTS

Examiner Initials	Cite No.	Document Number	Publication Date	Name of Patentee or Applicant	Reference to Related Case
	1	US 5,288,367	1994-02-22	Angell et al.	

## OTHER DOCUMENTS

Examiner Initials	Cite No.	Description	T
	2	ROBBINS et al., "An Investigation of the Plasma Chemistry Involved in the Synthesis of ZnO by PECVD," Journal of the Electrochemical Society, 150 (10), pp. C693-C698, 2003	
	3	WU et al., "Towards a Complete Plasma Diagnostic System," 4 pages total	
	4	SHUL et al., "Group-III Nitride Etch Selectivity in BCl <sub>3</sub> /Cl <sub>2</sub> ICP Plasmas," 11 pages total, MRS Internet J. Nitride Semicond. Res. 4S1, G8.1 (1999)	

Examiner Signature	Date Considered
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